

16cm Source

Our 16cm RF ion beam source is an industry workhorse, serving as the dominant deposition source in ion beam deposition (IBD) systems around the world. With an output capacity of 600mA, 800mA, or even 1000mA this dynamic and versatile source can satisfy a huge array of needs in deposition and large-scale Ion assist processes. Available with standard molybdenum, collimated graphite, or titanium grids, this source can be used in almost any type of contamination-sensitive ion beam process. This 16cm source can even be equipped with modulators allowing it to be used in metal deposition and etch processes, an operational regime normally challenging for RF ion beam. The source provides a 16cm ion beam which is then shaped by the choice of grids. Convergent, divergent, collimated, and even multi-focal point grids are available with this source. Please refer to the grid selection table below.



FLANGE/EXTENSION MOUNT

504903A

504424B

504854A

504891A

504855A

IBEAM 701-4

505914Cx

505311A

505752A

507128A

IBOX-104

504296B

5042961

507103A

504137A

504373B

504599A

504851A

504455A

504822A

Power Supplies IBEAM 703-1 series

Neutralizer

Neutralizer

RF Matching

RF Generator

Adapter Box

3 Focal Point

2 Focal Point

66cm FP, Div.

66cm FP.

Convergent

Collimated

33cm FP, Div.

GRID OPTIONS

Cable Kits

Common

Flanges

Internal Mount

2¾" CF RFN Flange

4.5" CF RFN Flange

6" CF RFN Flange

1000W RF Generator

Source RF

Molybdenum

Molybdenum

Molybdenum

Molybdenum

Molybdenum

Molybdenum

Titanium

Titanium

Graphite

RFN

The Flange and Extension Mount options for this ion source offer fixed positioning for maximum process repeatability. The Flange Mount places the source directly against the flange using the smallest amount of space, while the Extension Mount stands off the flange with fixed posts. The minimum flange size for these options is a 16.5-inch Conflat. These packages include a high-voltage cover on the atmosphere side of the flange to which the RF Matching Network mounts directly. Also provided are connection points for cooling water, source gas, and DC bias.





▲INTERNAL MOUNT

Using an Internal Mount configuration places the ion source loosely inside the vacuum chamber, allowing angular (pointing) adjustment to suit process needs. The maximum distance from the RF vacuum feedthrough for this configuration is 18-inches. This option allows some freedom of location of the ion source and the ability to use multiple smaller feedthroughs instead of one large feedthrough. The standard flanges for this configuration are three 2.75 inch Conflat. Other flange combinations are available. The RF Matching Network mounts directly to the RF feedthrough.

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NOMINAL PERFORMANCE DATA - USING ARGON @ 18 SCCM									
	BEAM			ACCELERATOR			RF POWER		NEUTRALIZER
Voltage (V)		Current (mA)		Voltage (V)	Current	(mA)	Forward (W)	Reflected (W)	Emission (mA)
250		300		550	11		199	0	450
500		300		400	8		193	0	450
750		450		300	17		266	0	675
1000		600		350	18		347	1	900
1250		600		250	15		352	2	900
1250		800		400	24		485	4	1200
1500		800		250	20		475	3	1200
250-1500		100 flo	or	200	~3		~94	1	150
OPTIONS & ACCESSORIES									
Ion Source		16RF08		Standard Ion Source		Used for 600mA Configuration			
		16RF HC		Advanced Ion Source		Required for 800mA and 1000mA configuration			
Interface Kits		504901A		Flange Mount		Includes Vacuum Feedthroughs and vacuum-side connections to source for RF Power, DC bias, cooling			
		504902A		Extension Mount					

water, and gas

1000mA / 1500V Beam configuration, requires separate RF Generator

3 grid, 104/72/40cm FPs, 0.065" spacing, .020" thick

3 grid, 104/72/40cm FPs, 0.065" spacing, .015" thick

3 grid, 104/72cm FPs, 0.065" spacing, .020" thick

3 grid, 104/72/40cm FPs, 0.065" spacing

I-Beam 703 Cable Kit with beam, RFN and RF cables

3 grid, 66cm FP, Divergent

3 grid, 66cm FP, Convergent

3 grid, 66cm FP, Convergent

3 grid, Graphite, flat

Moly, 3 grid, 33cm FP, Divergent

I-Beam 701/703 Cable Kit for use with 1kW RF Generator

Radio frequency – requires a mounting flange

RF Power, DC Bias, Control, and RFN Operation

Used only with I-Beam 701 power supplies

Includes Matching Network & Controller for source

Adapts connections to an Ion-Tech style configuration

Sputter

Sputter

Sputter

Sputter

Sputter

Sputter

Assist

Etch

Assist

Each flange has a RFN matching network.